

# Investigation into Memory Behavior on van der Waals Heterostructure for the Development of Neuromorphic Device



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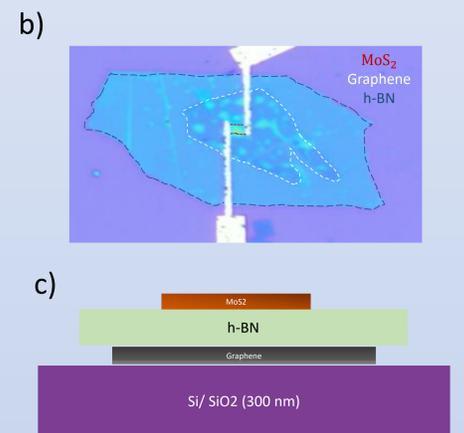
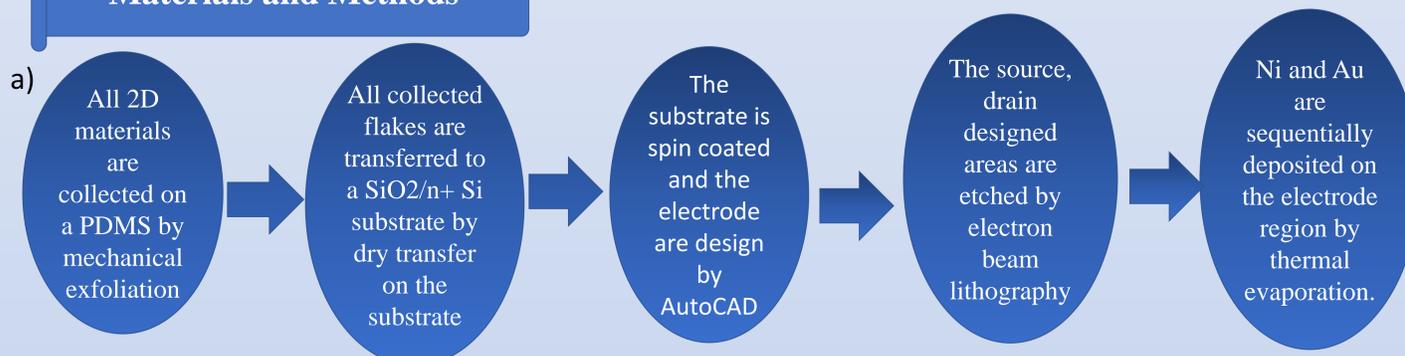
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## Abstract

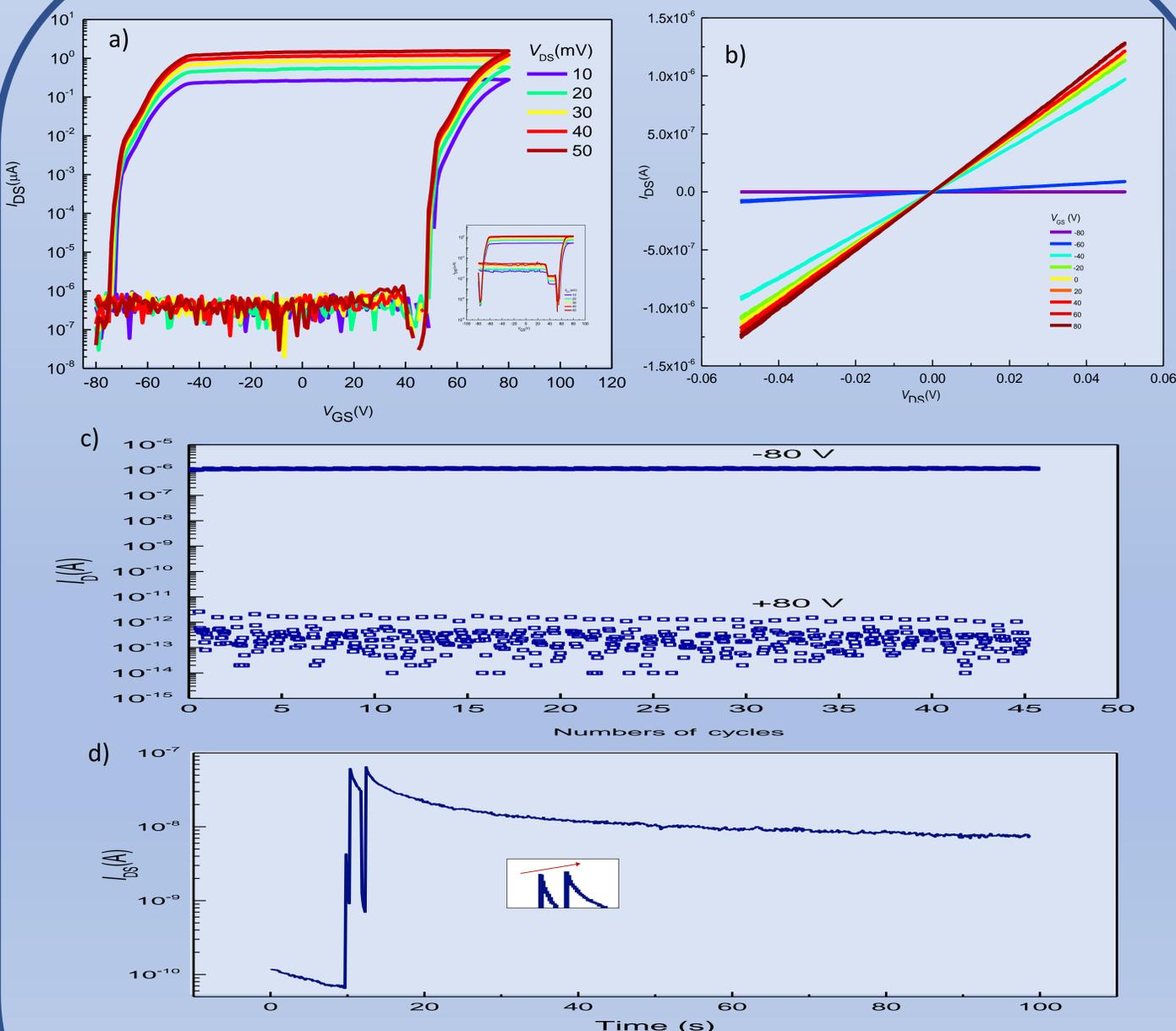
Neuromorphic computation has been developed using biological behavior as a model for computers for decades. The separated memory and data processing in neuromorphic devices based on traditional von Neumann architecture is not able enough to reach the satisfactory outcome of analog and continuous information processes in the brain. In this study, a van der Waals heterostructural field effect transistor (VH-FET) using graphene (Gr), hexagonal boron nitride (h-BN) and molybdenum disulfide (MoS<sub>2</sub>) was introduced with a high on/off ratio ( $\sim 10^6$ ) and endurance from  $\sim 50$  program/erase cycles. The hysteresis behavior of the VH-FET performed a huge memory window ( $\sim 120$  V) and non-volatile characteristics. Finally, the memory characteristic of VH-FET was applied in order to emulate neuromorphic behavior.

## Materials and Methods



**Figure 1.** a) Flow chart of the device fabrication process. b) Optical Microscopic image of the fabricated VH-FET. c) Schematic diagram of the fabricated device.

## Results and Discussions



**Figure 2.** a) The transfer curve in the  $V_{GS}$  sweeping range of  $\pm 80$  V with different  $V_{DS}$  values (Inset: transfer characteristics for thicker MoS<sub>2</sub>) b) Output characteristics shows ohmic nature with the  $V_{GS}$  variations c) The endurance nature to test the device durability and operability of the device d) paired-pulse facilitation of our VH-FET

## Conclusion

In summary, here we fabricated VH-FET which is able to show a high on/off ratio where the non-volatile memory property proves its utility as a memory device. With the channel layer thickness control, better performance of the device can be achieved.

## Acknowledgment

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## References

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